

AOMATT 2008

CALL FOR PAPER

The 4th International Symposium on Advanced Optical Manufacturing and Testing Technologies (AOMATT 2008) is to be held in Nov. 19-21, 2008 in the beautiful city of Chengdu, China.

AOMATT 2008 offers conference attendee the opportunity to see Chengdu and vicinities after the May 12, 2008 earthquake. Chengdu is also the gateway to Tibet. Attendee can take advantage of this opportunity to visit Tibet and the beautiful city of Lasha, China.

I. Important Date

Symposium Date: Nov. 19-21, 2008

Abstract Due: July 30, 2008

Manuscript Due: Oct. 15, 2008

II. Symposium Organization

Sponsored by:

COS- The Chinese Optical Society
IOE - Institute of Optics and Electronics, Chinese Academy of Sciences

Technical Co-sponsor :

SPIE - The International Society for Optical Engineering

Cooperating Organization:

Committee of Optical Manufacturing Technology, COS
State Key Lab. of Opt. Tech. for Microfabrication (China)
Sichuan Optical Society (SOS), China

Supported by:

Ministry of Science and Technology of China
Chinese Academy of Sciences (CAS)
National Natural Science Foundation of China

Honorary Chair:

WANG Daheng, Academician, Chinese Academy of Sciences and Chinese Academy of Engineering (China)

Symposium General Chair:

ZHOU Bingkun, President of Chinese Optical Society (COS), Academician, Chinese Academy of Sciences

Symposium General Co-Chair:

James C. Wyant, Director of Optical Sciences Center, Univ. of Arizona (USA)

CAO Jianlin, Vice Director, Ministry of Science and Technology of China

ZHANG Yudong, Director of the Institute of Optics and Electronics (IOE), Chinese Academy of Sciences

Please submit your abstract by

July 30, 2008 to:

Email: aomatt08@ioe.ac.cn

yangli@ioe.ac.cn

Web: www.ioe.ac.cn/aomatt2008/english

Organizing Committee:

ZHANG Yudong, Director of Institute of Optics and Electronics, CAS (China), Chair

CAO Jinghua, Deputy Director General of Bureau of International Cooperation, Chinese Academy of Science, *Co-Chair*

NI Guoqiang, Secretary General of Chinese Optical Society (COS), *Co-Chair*

Jos Benschop, System Engineering and Research, ASML (Netherland)

John M. Schoen, Center for Optical Manufacturing, University of Rochester (USA)

Edgar Bader, Lithographic Optics Division, Carl Zeiss SMT AG(Germany)

YANG Li, Committee of Optical Manufacturing Technology (COMT), COS (China)

Jinxue Wang, SPIE Technical Advisor (USA)

Eric RUCH, REOSC Optics, SAGEM (France)

Jim Burge, University of Arizona (USA)

David D. Walker, University College Landon (UK)

Yoshiharu Namba, Chubu University (Japan)

Hexin Wang, Optical Technology, Carl Zeiss AG (Germany)

Masaomi Kameyama, Nikon Corporation (Japan)

WU Fan, Institute of Optics and Electronics, CAS (China)

Rongbin Li, Hong Kong Polytechnic University (Hong Kong, China)

Tadashi Hatano, Tohoku University (Japan)

LI Jingzhen, Shenzhen University (China)

Mike DeMarco, QED Technologies (USA)

James R. Torley, University of Colorado (USA)

LI Xiaoping, Shanghai Micro Electronic Equipment Co. Ltd (China)

Robert Smythe, ZYGO Corporation (USA)

Richard Freeman, ZEEKO Ltd (UK)

Gaven Chapmam, Moore Precision Tool (USA)

Technical Program Committee:

YANG Hu, Vice director of Institute of Optics and Electronics, CAS (China), *Chair*

QIN Yuwen, Natural Science Foundation of China, *Co-Chair*

Sen Han, Veeco, Inc. (USA), *Co-Chair*

Myung K. Cho, NOAO (USA), *Co-Chair*

Bernard Delabre, ESO (Germany)

YU Huadong, Changchun University of Science and Technology (China)

Magomed Abdulkadyrov, Lytkarino Optical Glass Factory (Russia)

Jose M. Sasian, University of Arizona (USA)
Ming liu, Institute of Microelectronics, CAS (China)
XIN Qiming, Beijing Institute of Technology (China)
LI Wei, Chengdu Fine Precision Optical Engineering Research Centre (China)
Paul Klocek, ELCAN Optical Technologies (USA)
YU Jingchi, Suzhou University (China)
CHENG Xuemin, Tsinghua University (China)
ZHANG Xuejun, Changchun Institute of Fine Mechanics and Physics, CAS (China)
Mary G. Turner, InfoTek Information Systems (USA)
Han Changyuan, Optical Testing Technology Committee, COS (China)
Masahide Katsuki, Toshiba Machine Co. Ltd (Japan)
Liang Ying Chun, Harbin Institute of Technology (China)
Matthias Pfaff, OptoTech Optikmaschinen GmbH (Germany)
Michael Sander, Satisloh GmbH (Germany)
Thomas Danger, Schneider GmbH (Germany)
Mike Conroy, Taylor Hobson Limited (England)

Secretary General of the Symposium:

YANG Li, Committee of Optical Manufacturing Technology, COS (China)
Jinxue Wang, SPIE Technical Advisor (USA)

III. Conferences

Conference 1: Large Mirror and Telescopes

Conference Chairs:

JIANG Wenhan, Academician, Chinese Academy of Engineering (China)
Roland GEYL, REOSC Optics, SAGEM (France)
Myung K. Cho, National Optical Astronomy Observatory (USA)
WU Fan, Institute of Optics and Electronics, CAS (China)

Committee:

Jim Burge, University of Arizona (USA)
Bernard Delabre, ESO (Germany)
Eric RUCH, REOSC Optics, SAGEM (France)
Magomed Abdulkadyrov, Lytkarino Optical Glass Factory (Russia)
Matt Johns, Carnegie Observatories (USA)
Hans J. Kaercher, MAN Technologie AG (Germany)
YU Jingchi, Suzhou Univ. (China)
Sung-Kie Youn, Korea Advanced Institute of Science and Technology (KAIST) (Korea)
GAO Bilie, Nanjing Institute of Astronomical Optical Technology, CAS (China)

We invite you to submit papers on the following and related topics to this conference.

- Mirrors for large astronomical and space telescopes
- Light-weighted mirror technology

- Large deployable mirror and telescopes
- New and innovative mirror and telescope designs
- Advanced testing methods for large mirror
- Support systems and structures
- New material for large mirrors

Conference 2: Advanced Optical Manufacturing Technologies

Conference Chairs:

YANG Li, COMT, COS (China)
John Schoen, Center for Optical Manufacturing, University of Rochester (USA)
Yoshiharu Namba, Chubu University (Japan)
LI Shengyi, NUDT (China)

Committee:

David D. Walker, University College Landon (U.K)
Mike DeMarco, QED Technologies (USA)
XIN Qiming, Beijing Institute of Technology (China)
James Torley, University of Colorado(USA)
YU Jingchi, Suzhou University (China)
Masahide Katsuki, Toshiba Machine Co. Ltd (Japan)
Karen Scott, The Aerospace Corp (USA)
Gaven Chapmam, Moore Precision Tool (USA)
Richard Freeman, ZEEKO Ltd (UK)
Paul Shore, Cranfield University (UK)
Wenda Jiang, LPI Precision Optics Ltd. (Hong Kong)
HUI Changshun, Tianjin Jinhang Institute of Technology Physics (China)

Please submit papers on the following and related topics to this conference.

- Advanced optical manufacturing technologies
- Aspherical optics design, manufacturing and testing
- ICF optical technology and engineering
- Super-precision optical manufacturing
- Optical thin film coatings
- Diamond turning technology
- Optical design and simulation software and tool
- Optoelectronics components and modules integration and manufacturing
- Opto-mechanical components and devices

Conference 3: Optical Test and Measurement Technology and Equipments

Conference Chairs:

ZHANG Yudong, Director of Institute of Optics and Electronics, CAS (China)
James C. Wyant, Director of Optical Sciences Center, University of Arizona (USA)
Robert Smythe, ZYGO Corporation (USA)
Hexin Wang, Optical Technology, Carl Zeiss AG (Germany)

Committee:

LI Jingzhen, Shenzhen University (China)
Jose M. Sasian, University of Arizona (USA)

Tadashi Hatano, Tohoku University (Japan)
Mike Conroy, Taylor Hobson Limited (England)
SU Chaolian, Xi'an Institute of Technology (China)
James Torley, University of Colorado (USA)
XU Qiao, Chengdu Fine Optical Engineering Research Center (China)
Peter C. Chen, The Catholic University (USA)
Mary G. Turner, InfoTek Information Systems (USA)
HAN Changyuan, Changchun Institute of Optics, Fine Mechanics and Physics, CAS (China)
Malacara-Doblado Daniel, Centro de Investigaciones en Optica, A. C. (Mexico)
ARAF ALY, Chonnam National University (Korea)
Sondes Trabelsi-Bauer, Karlsruhe Research Center (Germany)

Please submit papers on the following and related topics to this conference.

- Modern interferometric technologies
- Test for aspherical optical surface
- Test for super-precision optical surface
- Measurement for super smooth surface
- Measurement of optical thin film
- Test with infrared technologies
- Optical contamination
- Optical test and measurement for nanometer technology
- New and innovative metrology and equipment
- Analysis and modeling tools and software

Conference 4: Design, Manufacturing and Testing of Micro and Nano Optical Devices and Systems

Conference Chairs:

Sen Han, Veeco, Inc. (USA)
Jos Benschop, System Engineering and Research, ASML (Netherlands)
Edgar Bader, Lithographic Optics Division, Carl Zeiss SMT AG (Germany)
Masaomi Kameyama, Nikon Corporation (Japan)
LUO Xiangang, Institute of Optics and Electronics, CAS (China)
LI Yanqiu, Beijing Institute of Technology (China)

Committee:

WANG Xiangchao, Shanghai Institute of Optics and Fine Mechanics, CAS (China).
LI Zhihong, MEMS Center, Beijing University (China)
Li-Anne Liew, National Institute of Science and Technology (USA)
Ming Liu, Institute of Microelectronics, CAS (China)
Yao Li, Centre for Composite Materials, Harbin Institute of Technology (China)
Tadashi Hatano, Tohoku University (Japan)
Zhichun Ma, Ford Motor Company (USA)
LI Xiaoping, Shanghai Micro Electronic Equipment Co Ltd (China)
Sung Moon, Korean Institute of Science and Technology

ZHAO Qingliang, Harbin Institute of Technology (China)
FANG Fengzhou, Tianjing University (China)

Papers on the following and related topics should be submitted to this conference.

- Micro-nano optical system design
- Micro-nano Optical manufacturing and testing
- Nano metrology technology and tools
- Nanoscale imaging and sensing technologies
- Nanofluidics device design, fabrication and testing
- Fabrication of MEMS/MOEMS devices
- Testing and Characterization of MEMS/MOEMS
- MEMS/MOEMS reliability
- Packaging of MEMS/MOEMS devices
- Next generation lithography
- EUVL research and development
- Advances in thin film coating for MEMS Microfluidics, BioMEMS, and Medical Microsystems

IV. Abstract Submission

Please submit your abstract to aomatt08@ioe.ac.cn. Your abstract submission must include all of the following:

1. PAPER TITLE

2. AUTHORS (principal author first)

For each author:

- First (given) Name (initials not acceptable)
- Last (family) Name
- Affiliation
- Mailing Address
- Telephone Number
- Fax Number
- Email Address

3. PRESENTATION PREFERENCE

"Oral Presentation" or "Poster Presentation"

4. PRINCIPAL AUTHOR'S BIOGRAPHY

Approximately 50 words.

5. ABSTRACT TEXT Approximately 300 words.

6. KEYWORDS Maximum of five keywords

V. Hotel Information

Please check <http://www.ioe.ac.cn/aomatt2008/english> for hotel information and update.

VI. Registration Information

Please check <http://www.ioe.ac.cn/aomatt2008> for registration information and download registration forms.

VII. Visa Information

For visa application letter and information, please send e-mail to zhailin@hotmail.com. Please consult your travel agent or overseas Chinese Consulate web site for visa requirements. If you plan to tour before or after the

conference, you may apply for a tourist visa that does not need visa invitation letter.

Contact:

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**For updated symposium information, registration,
hotel, etc., please visit symposium web page at
www.ioe.ac.cn/aomatt2008/english/**